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(54) Title: PHOTSENSITIVE RESIN COMPOSITION, METHOD OF FORMING LEVEL DIFFERENCE PATTERN USING THE PHOTSENSITIVE RESIN COMPOSITION, AND METHOD OF PRODUCING INK JET HEAD

(57) Abstract: To provide a positive type photosensitive resin composition, containing at least an acrylic resin having a carboxylic anhydride structure in a molecule, and a compound that generates an acid when irradiated with light.

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